

ABSTRACT

Provided is a sputtering target capable of reducing generation of particles, and a method for producing the same. The sputtering target includes: 10 mol% or more and 85 mol% or less of Co, 0 mol% or more and 47 mol% or less of Pt, and 0 mol% or more and 47 mol% or less of Cr, as metal components; and at least B₆O as an oxide component.